

## ABSTRACT

A lithographic apparatus including an illumination system for providing a beam of radiation and a support structure for supporting a patterning device. The patterning device serving to impart the beam with a pattern in its cross-section. The apparatus also having a substrate table for holding a substrate and a projection system for projecting the patterned beam onto a target portion of the substrate. The lithographic apparatus further having a chuck for supporting an object and a frame which supports the chuck with respect to other parts of the lithographic apparatus. The chuck is thermally isolated from at least the frame.